

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L19	67	(alignment or registration) near layers same (wafer or semiconduct?r) same Image	USPAT	OR	ON	2006/02/13 11:39
L20	75	(measur\$5 or detect\$4 or inspect\$5) near2 (alignment or registration) with (features or circuits) with layers	USPAT	OR	ON	2006/02/13 11:40

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L19	67	(alignment or registration) near layers same (wafer or semiconductor) same image	USPAT	OR	ON	2006/02/13 11:39
L20	75	(measure\$5 or detect\$4 or inspect\$5) near2 (alignment or registration) with (features or circuits) with layers	USPAT	OR	ON	2006/02/13 12:02
L21	37	(measure\$5 or detect\$4 or inspect\$5) near2 (alignment or registration) same layers near2 (semiconductor or wafer or reticle or mask) and image near2 (feature or circuit or pattern) with layer	USPAT	OR	ON	2006/02/13 12:09
L22	22	(measure\$5 or detect\$4 or inspect\$5) near2 (alignment or registration) same layers near2 (semiconductor or wafer or reticle or mask) and image near2 (feature or circuit or pattern) with layer	US-PGPUB; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/13 12:14
L23	416	(382/151).CCLS.	USPAT	OR	OFF	2006/02/13 12:14
L24	1322	((382/151) or (348/87) or (356/237.5) or (438/7)).CCLS.	USPAT	OR	OFF	2006/02/13 12:15
L25	19	24 and (alignment or registration) near layers	USPAT	OR	ON	2006/02/13 12:15
L26	19	24 and (alignment or registration) near layer	USPAT	OR	ON	2006/02/13 12:15

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	0	((measur\$5 or detect\$4 or inspect\$5) near2 (alignment or registration) same layers near2 (semiconduct?r or wafer or reticle or mask) and image near2 (feature or circuit or pattern) with layer).clm.	US-PGPUB	OR	ON	2006/02/13 13:47
L2	1	((measur\$5 or detect\$4 or inspect\$5) near2 (alignment or registration) same layers near2 (semiconduct?r or wafer or reticle or mask) and image near2 (feature or circuit or pattern) with layer).clm.	US-PGPUB	OR	ON	2006/02/13 13:47
L3	81	((measur\$5 or detect\$4 or inspect\$5) and (alignment or registration) and layer and (semiconduct?r or wafer or reticle or mask) and image and (feature or circuit or pattern)).clm.	US-PGPUB	OR	ON	2006/02/13 13:48
L4	0	((measur\$5 or detect\$4 or inspect\$5) and (alignment or registration) and layer and (semiconduct?r or wafer or reticle or mask) and image and (feature or circuit or pattern) and metrological).clm.	US-PGPUB	OR	ON	2006/02/13 13:48